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CHAPTER 2

Continuity equation

2.9. Continuity equation

<u>2.9.1. Derivation</u>
<u>2.9.2. The diffusion equation</u>
<u>2.9.3. Steady state solution to the diffusion equation</u>

The continuity equation describes a basic concept, namely that a change in carrier

density over time is due to the difference between the incoming and outgoing flux of

carriers plus the generation and minus the recombination.

The flow of carriers and recombination and generation rates are illustrated with

Figure 2.9.1.



Figure 2.9.1 : Electron currents and possible recombination and generation processes

 \Box The rate of change of the carriers between x and x + dx equals the difference

between the incoming flux and the outgoing flux plus the generation and minus the

recombination:

$$\frac{\partial n(x,t)}{\partial t}A\,dx = \left(\frac{J_n(x)}{-q} - \frac{J_n(x+dx)}{-q}\right)A + \left(G_n(x,t) - R_n(x,t)\right)A\,dx \tag{2.9.1}$$

 \Box where n(x,t) is the carrier density, A is the area, $G_n(x,t)$ is the generation rate and

 $R_n(x,t)$ is the recombination rate. Using a Taylor series expansion,

$$J_{n}(x + dx) = J_{n}(x) + \frac{d J_{n}(x)}{dx} dx$$
(2.9.2)

This equation can be formulated as a function of the derivative of the current:

$$\frac{\partial n(x,t)}{\partial t} = \frac{1}{q} \frac{\partial J_n(x,t)}{\partial x} + G_n(x,t) - R_n(x,t)$$
(2.9.3)

and similarly for holes one finds:

$$\frac{\partial p(x,t)}{\partial t} = -\frac{1}{q} \frac{\partial J_p(x,t)}{\partial x} + G_p(x,t) - R_p(x,t)$$
(2.9.4)

A generalization in three dimensions yields the following continuity equations for electrons and

holes:

$$\frac{\partial n(x, y, z, t)}{\partial t} = \frac{1}{q} \vec{\nabla} \vec{J}_{n}(x, y, z, t) + G_{n}(x, y, z, t) - R_{n}(x, y, z, t)$$
(2.9.7)
$$\frac{\partial p(x, y, z, t)}{\partial t} = -\frac{1}{q} \vec{\nabla} \vec{J}_{y}(x, y, z, t) + G_{y}(x, y, z, t) - R_{y}(x, y, z, t)$$
(2.9.8)



p–n Junction

- ► 3.1 THERMAL EQUILIBRIUM CONDITION
- **3.2 DEPLETION REGION**
- > 3.3 DEPLETION CAPACITANCE
- 3.4 CURRENT-VOLTAGE CHARACTERISTICS
- ► 3.5 CHARGE STORAGE AND TRANSIENT BEHAVIOR
- **3.6 JUNCTION BREAKDOWN**
- > 3.7 HETEROJUNCTION
- SUMMARY

► In the preceding chapters we considered the carrier concentrations and transport phenomena in homogeneous semiconductor materials.

> In this chapter we discuss the behavior of single-crystal semiconductor material containing both p- and n-type regions that form a p-n junction.

> A p-n junction serves an important role both in modern electronic applications and in

understanding other semiconductor devices.

> It is used extensively in rectification, switching, and other operations in electronic

circuits.

> It is a key building block for the bipolar transistor and thyristor (Chapter 4), as well as for

metal-oxide semiconductor field-effect transistors (MOSFETs) (Chapters 5 and 6).

 \geq Given proper biasing conditions or when exposed to light, the p-n junction also

functions as either a microwave (Chapter 8) or photonic device (Chapters 9 and 10).

► We also consider a related device—the heterojunction, which is a junction formed between two dissimilar semiconductors.

➢ It has many unique features that are not readily available from the conventional p−n junction.

>The heterojunction is an important building block for heterojunction bipolar transistors

(Chapter 4), modulation doped field-effect transistors (Chapter 7), quantum-effect devices

(Chapter 8), and photonic devices (Chapters 9 and 10).

> Specifically, we cover the following topics:

• The band diagram of a p–n junction at thermal equilibrium.

• The behavior of the junction depletion layer under voltage biases.

• The current transport in a p-n junction and the influence of the generation and

recombination processes.

• The charge storage in a p-n junction and its influence on the transient behavior.

• The avalanche multiplication in a p-n junction and its impact on the maximum reverse

voltage

• The heterojunction and its basic characteristics.

3.1 THERMAL EQUILIBRIUM CONDITION

>The most important characteristic of p–n junctions is that they rectify: that is, they allow

current to flow easily in only one direction.

>Figure 1 shows the current-voltage characteristics of a typical silicon p–n junction.



Fig. 1 Current-voltage characteristics of a typical silicon p-n junction.

> When we apply "forward bias" to the junction (i.e., positive voltage on the p-side), the current

increases rapidly as the voltage increases.

> However, when we apply a "reverse bias," virtually no current flows initially.

> As the reverse bias is increased the current remains very small until a critical voltage is reached, at which point the current suddenly increases.

> This sudden increase in current is referred to as the junction breakdown.

>The applied forward voltage is usually less than 1V, but the reverse critical voltage, or

breakdown voltage, can vary from just a few volts to many thousands of volts, depending on

the doping concentration and other device parameters.

3.1.1 Band Diagram

>In Fig. 2a, we see two regions of p- and n-type semiconductor materials that are

uniformly doped and physically separated before the junction is formed.

> Note that the Fermi level E_F is near the valence band edge in the p-type material and near the conduction band edge in the n-type material.

➤While p-type material contains a large concentration of holes with few electrons, the opposite is true for n-type material.



Fig. 2 (a) Uniformly doped p-type and n-type semiconductors before the junction is formed. (b) The electric field in the depletion region and the energy band diagram of a p-n junction in thermal equilibrium.

>When the *p*- and *n*-type semiconductors are jointed together, the large carrier

concentration gradients at the junction cause carrier diffusion.

> Holes from the *p*-side diffuse into the *n*-side, and electrons from the *n*-side diffuse into the *p*-side.

> As holes continue to leave the p-side, some of the negative acceptor ions (N_{+}

) near the junction are left uncompensated because the acceptors are fixed in

the semiconductor lattice, whereas the holes are mobile.

>Similarly, some of the positive donor ions ($N_{D_{\tau}}$) near the junction are left

uncompensated as the electrons leave the *n*-side.

>Consequently, a negative space charge forms near the *p*-side of the junction and a

positive space charge forms near the *n*-side.

>This space charge region creates an electric field that is directed from the positive

charge toward the negative charge, as indicated in the upper illustration of Fig. 2b.

> The lower illustration of Fig. 2b shows that the hole diffusion current flows from left

to right, whereas the hole drift current due to the electric field flows from right to

left.

 \geq The electron diffusion current also flows from right to left, whereas the electron

drift current flows in the opposite direction.

Animations: <u>https://www.pveducation.org/pvcdrom/pn-junctions/formation-of-a-pn-junction</u> https://www.pveducation.org/pvcdrom/pn-junctions/p-n-junction-diodes

3.1.2 Equilibrium Fermi Levels

>At thermal equilibrium, i.e. the steady-state condition at a given temperature with no

external excitations, the individual electron and hole currents flowing across the

junctions are identically zero.

> Thus, for each type of carrier the drift current due to the electric field must exactly

cancel the diffusion current due to the concentration gradient.

From Eq. 32 in Chapter 2,

$$J_{p} = J_{p}(\operatorname{drift}) + J_{p}(\operatorname{diffusion})$$
$$= q\mu_{p}p \mathscr{E} - qD_{p}\frac{dp}{dx}$$
$$= q\mu_{p}p\left(\frac{1}{q}\frac{dE_{i}}{dx}\right) - kT\mu_{p}\frac{dp}{dx} = 0,$$

About final derivation:

(first why
$$\mathscr{E} = \frac{1}{q} \frac{dE_i}{dx}$$

Consider conduction in a homogeneous semiconductor material.

(1)

➢Figure 4a shows an n-type semiconductor and its band diagram at thermal equilibrium.

 \succ Figure 4b shows the corresponding band diagram when a positive biasing voltage is

applied to the right-hand terminal.

>When an electric field *E* is applied to a semiconductor, each electron will experience

a force -qE from the field. The force is equal to the negative gradient of potential

 $(\)$

energy; that is,

$$-q \mathscr{E} = -(\text{gradient of electron potential energy}) = -\frac{dE_C}{dx}$$
.



Fig. 4 Conduction process in an n-type semiconductor (a) at thermal equilibrium and (b) under a biasing condition.

>Recall that in Chapter 1, the bottom of the conduction band E_c corresponds to 1

the potential energy of an electron.

Since we are interested in the gradient of the potential energy, we can use any part of the band diagram that is parallel to E_c (e.g., E_r , E_r , or E_v , as shown in Fig. 4*b*).

> It is convenient to use the intrinsic Fermi level E_i because we shall use E_i

when we consider p-n junctions.

>Therefore, from Eq. 7 we have

$$\mathscr{E} = \frac{1}{q} \frac{dE_C}{dx} = \frac{1}{q} \frac{dE_i}{dx}.$$
(8)

 \geq We can define a related quantity ψ as the *electrostatic potential* whose

negative gradient equals the electric field:

$$\bullet \qquad \mathscr{E} \equiv -\frac{d\psi}{dx}.$$

(9)

Comparison of Eqs. 8 and 9 gives

$$\psi = -\frac{E_i}{q},\tag{10}$$

>which provides a relationship between the electrostatic potential and the

potential energy of an electron.

> For the homogeneous semiconductor shown in Fig. 4*b*, the potential energy

and E_{i} , decrease linearly with distance; thus, the electric field is a constant in the negative *x*-direction.

Its magnitude is the applied voltage divided by the sample length.

> The electrons in the conduction band move to the right side, as shown in Fig. 4b.

The kinetic energy corresponds to the distance from the band edge (i.e., E_C for electrons).

> When an electron undergoes a collision, it loses some or all of its kinetic energy to the lattice and drops toward its thermal equilibrium position.

>After the electron has lost some or all its kinetic energy, it will again begin to move

toward the right and the same process will be repeated many times.

> Conduction by holes can be visualized in a similar manner but in the opposite

(second why
$$D_n = \left(\frac{kT}{q}\right)\mu_n$$
)

We can write

$$\frac{1}{2}m_n v_{th}^2 = \frac{1}{2}kT.$$
(28)

$$D_n = \upsilon_{th} l = \upsilon_{th} (\upsilon_{th} \tau_c) = \upsilon_{th}^2 \left(\frac{\mu_n m_n}{q}\right) = \left(\frac{kT}{m_n}\right) \left(\frac{\mu_n m_n}{q}\right), \quad (29)$$

$$D_n = \left(\frac{kT}{q}\right) \mu_n.$$
(30)

Equation 30 is known as the Einstein relation. It relates the two important constants (diffusivity and mobility) that characterize carrier transport by diffusion and by drift in a semiconductor. The Einstein relation also applies between D_p